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(71) Applicant (for all designated States except US): DE-
GUSSA AG [DE/DE]; Bennigsenplatz 1, 40474 Düssel-
dorf (DE).

(72) Inventors; and

(75) Inventors/Applicants (for US only): SCHUMACHER,

Kai [DE/DE]; Berliner Strasse 16, 65719 Hofheim (DE).
OSWALD, Monika [DE/DE]; Burgallee 6c, 63454 Hanau
(DE).

(74) Common Representative: DEGUSSA AG; Intellectual
Property Management, PATENTE und MARKEN, Stan-
dort Hanau, Postfach 13 45, 63403 Hanau (DE).

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(54) Title: SILICON DIOXIDE DISPERSION



(57) **Abstract:** Stable, aqueous dispersion contain-
ing silicon dioxide powder having a hydroxyl group
density of 2.5 to 4.7 OH/nm², which is obtained from
a silicon dioxide powder produced by a flame hydrol-
ysis process under acid conditions. The dispersion is
produced by incorporating the silicon dioxide pow-
der into an aqueous solution by means of a dispersing
device. The dispersion can be used to produce glass
articles.

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